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ABSTRACT OF THE DISCLOSURE

*Please replace the text of the abstract of the disclosure  
currently on file with the following text:*

A semiconductor manufacturing apparatus, composed in part of  
a vacuum vessel, is capable of uniform processing of a substrate  
while occupying a small floor area and being readily  
maintainable. The apparatus includes at least one substrate  
stage provided on a vacuum vessel bottom plate and a cylinder  
surrounding the substrate stage. At least one cylinder  
lifting/lowering mechanism per cylinder is provided, in order to  
separate a space inside the cylinder, composing a processing  
chamber for processing the substrate surface, from a space  
outside the cylinder, composing a transport chamber for  
transferring the substrate. The transport chamber is provided  
with a substrate conveyer mechanism.